

<b>Form PTO-1449</b> (modified)		Atty. Docket No. 97-0008.02	Serial No. Unknown
List of Patents and Publications for Applicant's  <b>INFORMATION DISCLOSURE STATEMENT</b>  (Use several sheets if necessary)		Applicant Bradley J. Howard	
		Filing Date: Herewith	Group: Unknown
U.S. Patent Documents See Page 1	Foreign Patent Documents N/A	Other Art See Page 1	

**U.S. Patent Documents**

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date if App.
SJL	A1	4,921,321	5/1/90	Weidman	385	130	
	A2	5,439,780	8/8/95	Joshi et al.	430	296	
	A3	5,215,861	6/1/93	Augustino et al.	430	210-1	
	A4	4,978,594	12/18/90	Bruce et al.	430	14	
✓	A5	5,885,751	3/23/99	Weidman et al.	430	315	

**Foreign Patent Documents**

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
	B1						

**Other Art (Including Author, Title, Date Pertinent Pages, Etc.)**

Exam. Init.	Ref. Des.	Citation
SJL	C1	Ajey M. Joshi et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography," <i>SPIE</i> , Vol. 1925, pp. 709-720, January 1993.
	C2	O. Joubert et al., "Plasma polymerized - dry resist process for 0.25 $\mu$ m photolithography," <i>J. Vac. Sci. Technol. B</i> 12(6), pp. 3909-3913, Nov/Dec 1994.
	C3	O. Joubert et al., "Plasma Polymerized Organosilane Network Polymers; High Performance Resists for Positive and Negative Tone Deep UV Lithography," <i>SPIE</i> , Vol. 2195, pp. 358-371, May 1994.
	C4	T. W. Weidman et al., Applications of Plasma Polymerized Methylsilane as a Resist and Silicon Dioxide Precursor for 193 and 248 nm Lithography," <i>SPIE</i> , Vol. 2438, pp. 496-512, June 1995.
✓	C5	Timothy W. Weidman and Ajey M. Joshi, "New photodefinable glass etch masks for entirely dry photolithography: Plasma deposited organosilicon hydride polymers," <i>Appl. Phys. Lett.</i> 62(4), pp. 372-374, January 25, 1993

Examiner:

Date Considered:

12-12-04

EXAMINER: initial if reference considered, whether or not citation is in conformance with MPEP609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.